

METHOD OF FILM DEPOSITION, AND FABRICATION OF STRUCTURES

ABSTRACT OF THE DISCLOSURE

11 A method of fabricating aluminum oxide films utilizing
 aluminum alkoxide precursors is described. The aluminum
 oxide film is formed by (a) providing an aluminum
 alkoxide precursor that is dissolved, emulsified or
 suspended in a liquid; (b) providing a vapor generated
16 from the aluminum alkoxide precursor; and (c) depositing
 an aluminum oxide film on the substrate at a temperature
 greater than 500°C.

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